

Surface chemical analysis — Secondary-ion mass spectrometry — Method for depth profiling of boron in silicon

ICS 71.040.40

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National foreword

This British Standard reproduces verbatim ISO 17560:2002 and implements it as the UK national standard.

The UK participation in its preparation was entrusted to Technical Committee CII/60, Surface chemical analysis, which has the responsibility to:

- aid enquirers to understand the text;
- present to the responsible international/European committee any enquiries on the interpretation, or proposals for change, and keep the UK interests informed;
- monitor related international and European developments and promulgate them in the UK.

A list of organizations represented on this committee can be obtained on request to its secretary.

Cross-references

The British Standards which implement international publications referred to in this document may be found in the *BSI Catalogue* under the section entitled “International Standards Correspondence Index”, or by using the “Search” facility of the *BSI Electronic Catalogue* or of British Standards Online.

This publication does not purport to include all the necessary provisions of a contract. Users are responsible for its correct application.

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This British Standard, having been prepared under the direction of the Materials and Chemicals Sector Policy and Strategy Committee, was published under the authority of the Standards Policy and Strategy Committee on 28 August 2002

Summary of pages

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Surface chemical analysis — Secondary-ion mass spectrometry — Method for depth profiling of boron in silicon

*Analyse chimique des surfaces — Spectrométrie de masse des ions
secondaires — Dosage du bore dans le silicium par profilage d'épaisseur*



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Foreword

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International Standard ISO 17560 was prepared by Technical Committee ISO/TC 201, *Surface chemical analysis*, Subcommittee SC 6, *Secondary ion mass spectrometry*.

Annex A of this International Standard is for information only.